

 <p>INFORMATION DISCLOSURE STATEMENT</p> <p>BY APPLICANT</p>	Docket: 6047-53173	App: 09/590 795
	Applicant: Vishnu K. Agarwal et al.	
	Filed: June 8, 2000	Art Unit:

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U.S. PATENT DOCUMENTS

Init.*	Number	Date	Name	Class	Sub	Filed
DV	6,060,367 ✓	5/9/00	Sze			
	6,060,351 ✓	5/9/00	Parekh et al.			
	6,049,101 ✓	4/11/00	Graettinger et al.			
	6,037,220 ✓	3/14/00	Chien et al.			
	6,015,743 ✓	1/18/00	Zahurak et al.			
	5,962,065 ✓	10/5/99	Weimer et al.			
	5,985,714 ✓	11/16/99	Sandhu et al.			
	5,959,327 ✓	9/28/99	Sandhu et al.			
	5,877,063 ✓	3/2/99	Gilchrist			
	5,696,014 ✓	12/9/97	Figura			
	5,612,560 ✓	3/18/97	Chivukula et al.			
	5,608,247 ✓	3/4/97	Brown			
	5,427,974 ✓	6/27/95	Lur et al.			
	5,372,962 ✓	12/13/94	Hirota et al.			
	5,342,800 ✓	8/30/94	Jun			
DV	5,318,920 ✓	6/7/94	Hayashide			

EXAMINER: *Bhuland*

DATE *09/27/01*

*Examiner: Initial if considered, whether or not in conformance with MPEP 60;
draw line through cite if not in conformance and not considered. Send copy.

<div style="display: flex; align-items: center;"> <div style="border: 1px solid black; border-radius: 50%; padding: 10px; text-align: center; margin-right: 10px;"> O I P E SEP 12 2000 PATENT & TRADEMARK OFFICE </div> <div> INFORMATION DISCLOSURE STATEMENT BY APPLICANT </div> </div>				Docket: 6047-53173		App: 09/590,795	
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Init.*		Number	Date	Name	Class	Sub	Filed
DV		5,130,885✓	7/14/92	Fazan et al.	X	X	—
DV		5,068,199✓	11/26/91	Sandhu			—
FOREIGN PATENT DOCUMENTS							
		Number	Date	Country	Class	Sub	
OTHER DOCUMENTS							
DV			Kawahara, Takaaki et al., "(Ba, Sr)TiO ₃ Films Prepared by Liquid Source Chemical Vapor Deposition on Ru Electrodes," <u>Jpn. J. Appl. Phys.</u> , <u>35</u> :4880-4885 (1996).				
EXAMINER: <i>fvuland</i>				DATE <i>09/27/01</i>			
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U.S. PATENT DOCUMENTS

Init.*	Number	Date	Name	Class	Sub	Filed
DV	5,852,307	12/22/98	Aoyama et al.			

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DV	Kaga et al., "Thermal Stability of RuO ₂ Thin Films and Effects of Annealing Ambient on Their Reduction Process," <u>Jpn. J. Appl. Phys.</u> 38:3689-3692 (June 15, 1999).
DV	Hayashide et al., "Fabrication of Storage Capacitance-Enhanced Capacitors with a Rough Electrode," <u>Jpn. J. Appl. Phys.</u> , pp. 869-872 (1990).
DV	Matsui et al., "Thermal Stability of a RuO ₂ Electrode Prepared by DC Reactive Sputtering", <u>Jpn. J. Appl. Phys.</u> 39:256-263 (January 15, 2000).

EXAMINER: *Freeland*DATE *09/25/02*

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INFORMATION DISCLOSURE STATEMENT

BY APPLICANT

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Art Unit: 2811

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	5,923,999	7/13/99	Balasubramanyam et al.			/
	6,294,807	9/25/01	Chittipeddi et al.			/
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	4,851,895	7/25/89	Green et al.			/
	6,365,502	4/2/02	Paranjpe et al.			/
DV	6,409,904	6/25/02	Uzoh et al.			/

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EXAMINER: *Andrzej*

DATE 03/19/03

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